



07/25/00

Class	Subclass
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99	99.1
100	100.1

## THE CLASSIFICATION

• PARENT NUMBER •

**U.S. UTILITY Patent Application**

**O.I.P.E.**

PATENT DATE
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SCANNED

Am'

Q.A. 

APPLICATION NO.  
09/624712

CONT/PRIOR:

**CLASS**  
**430**

SUBCLASS

ART UNIT  
1756

**EXAMINER**

ANTISUBSIPAKTION:  
Jung Bang

Method for an improved developing process in wafer photolithography

PTO-2040  
12/88

**ISSUING CLASSIFICATION**

[illegible]

## TERMINAL DISCLAIMER

## DRAWINGS

**CLAIMS ALLOWED**

**Sheets Drwg.**

Figs. Drwg.

Printed by

Total Claims

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Print Claim for O.G.

☐ The term of this patent subsequent to \_\_\_\_\_ (date) has been disclaimed.

☐ The term of this patent shall not extend beyond the expiration date of U.S. Patent No. \_\_\_\_\_

☐ The terminal \_\_\_\_ months of this patent have been disclaimed.

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